IMAPR 2 6 2004 ESTATES PATENT AND TRADEMARK OFFICE

In re application of : Confirmation No. 8121

Kazuyuki NITTA et al. : Docket No. 2001_1143A

Serial No. 09/928,430 : Group Art Unit 1752

Filed August 14, 2001 : Examiner S. Lee

POSITIVE-WORKING PHOTORESIST COMPOSITION AND RESIST PATTERNING METHOD USING SAME

SUPPLEMENTAL RESPONSE

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

Further to the Response filed on April 12, 2004, please amend the present application as follows: